# STUDIES ON CORRELATION BETWEEN ELECTRONIC STRUCTURE AND ELECTRONIC CONDUCTIVITY IN MoX<sub>2</sub> (X = S, Se and Te)

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Thesis submitted in fulfillment of the requirements for the award of the degree of Bachelor of Applied Science (Honor) Material Technology

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### SUPERVISORS' DECLARATION

I hereby declare that I have checked the thesis and in my opinion, this thesis is adequate in terms of scope and quality for the award of the degree of Bachelor of Applied Science (Honor) Material Technology.

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## STUDENT'S DECLARATION

I hereby declare that the work in this thesis is my own except for quotations and summaries which have been duly acknowledged. The thesis has not been accepted for any degree and is not concurrently submitted for award of other degree.

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## **DEDICATION**

Special Dedication to my supervisor, my family members, my friends and all faculty members for all your care, support and believe in me.

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## LIST OF SYMBOLS

~	-	approximately
%	-	percent
λ	-	wavelength
$a_0$	-	Exciton Bohr radius
Å	-	angstrom (10 <sup>-10</sup> )
Å <sup>3</sup>	-	volume
t- <sub>ML</sub>	-	monolayer thickness
<i>t</i> -Offset	-	thickness offset
$E_{g-\mathrm{ML}}$	-	monolayer bandgap
$E_{g ext{-Offset}}$	-	bandgap offset
σ	-	conductivity

## LIST OF ABBREVIATIONS

EC	-	electrochemical capacitor
PC	-	pseudocapacitor
EDLC	-	electrochemical double layer capacitance
SSC	-	symmetric supercapacitor
ASC	-	asymmetric supercapacitor
AC	-	activated carbon
GPS	-	global positioning system
HF	-	Hartree-Fock
B3LYP	-	Becke, 3-parameter, Lee-Yang-Parr.
DFT	-	Density Functional Theory
CIF	-	Crystallographic information file
PBC	-	Periodic Boundary Conditions
НОМО	-	highest occupied molecular orbital
LUMO	-	lowest unoccupied molecular orbital